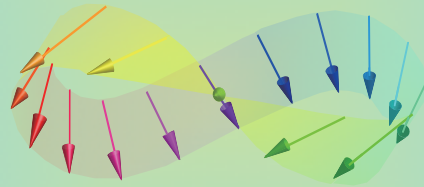


Semiconductor Devices

22



Atsufumi Hirohata

Department of Electronics

THE UNIVERSITY of York



11:00 Monday, 24/November/2014 (P/L 005)



Exercise 1

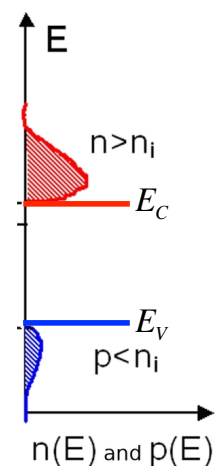
Find the probability of occupation of a level of 0.05 eV above the conduction band edge of a Silicon device if the Fermi level is 0.7 eV above the valence band edge.

Assume the bandgap (E_g) of Silicon is 1.1 eV and the effective mass of electron in Silicon is

$$0.40 \times (0.91 \times 10^{-30} \text{ kg}).$$

The Boltzmann constant (k_B) is 1.4×10^{-23} J/K, the Planck constant is 6.6×10^{-34} J-s and the temperature is 300K.

Use the conversion ratio: $1 \text{ eV} = 1.6 \times 10^{-19} \text{ J}$.





Answer to Exercise 1

Carrier density can be defined by

$$n =$$

Here, the effective density of states at the conduction band is defined as

$$N_C =$$

where m_e is the effective mass of electron.

$$\begin{aligned}
n &= 2 \left(\frac{2\pi \cdot 0.40 \times 0.91 \times 10^{-30} [\text{kg}] \cdot 1.4 \times 10^{-23} [\text{J/K}] \cdot 300 [\text{K}]}{(6.6 \times 10^{-34} [\text{J} \cdot \text{s}])^2} \right)^{3/2} \\
&\times \exp \left(\frac{\{0.7 - (1.1 + 0.05)\} [\text{eV}] \cdot 1.6 \times 10^{-19} [\text{J}]}{1.4 \times 10^{-23} [\text{J/K}] \cdot 300 [\text{K}]} \right) \\
&= 2 \left(2.21 \dots \times 10^{16} [\text{kg/J} \cdot \text{s}^2] \right)^{3/2} \cdot \exp(-17.1) \\
&= 2 \left(2.21 \dots \times 10^{16} [\text{m}^{-2}] \right)^{3/2} \cdot \exp(-17.1) \quad [\text{J}] = [\text{kg} \cdot \text{m}^2 / \text{s}^2] \\
&= 6.55 \dots \times 10^{24} \cdot 3.74 \dots \times 10^{-8} = 2.44 \dots \times 10^{17} [\text{m}^{-3}] \\
&\approx '
\end{aligned}$$

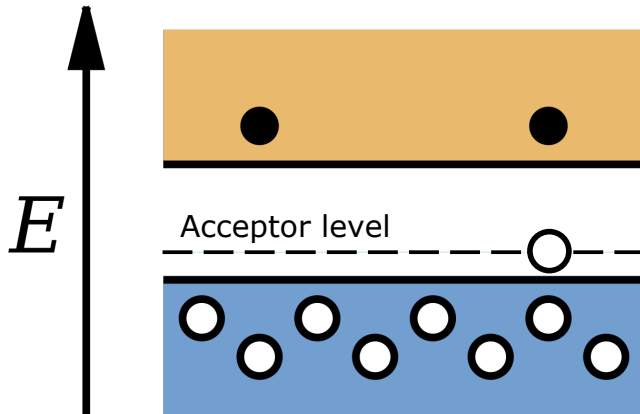
22 Extrinsic Semiconductor

- Doping
- Donor / acceptor
- Carrier density

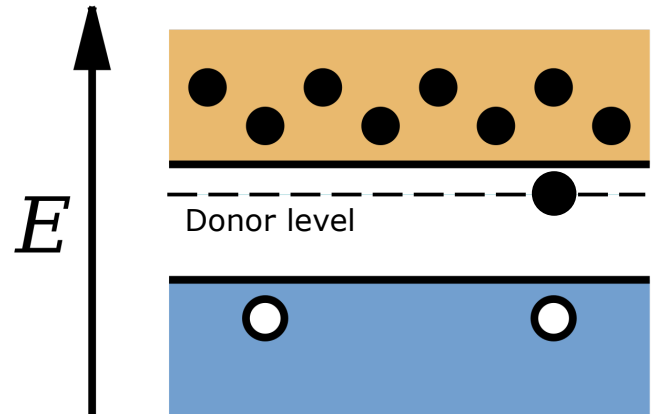


Extrinsic Semiconductors

p-type band structures :



n-type band structures :



Group IV semiconductors:

()
 ()

Group IV semiconductors:

()
 ()

Group III-V semiconductors:

GaAs and GaN
 (): Be, Zn, Cd and Ge

Group III-V semiconductors:

GaAs and GaN
 (): Se, Te, Si and Ge

* <http://www.wikipedia.org/>



Atomic Structure of *p*-Type Semiconductors

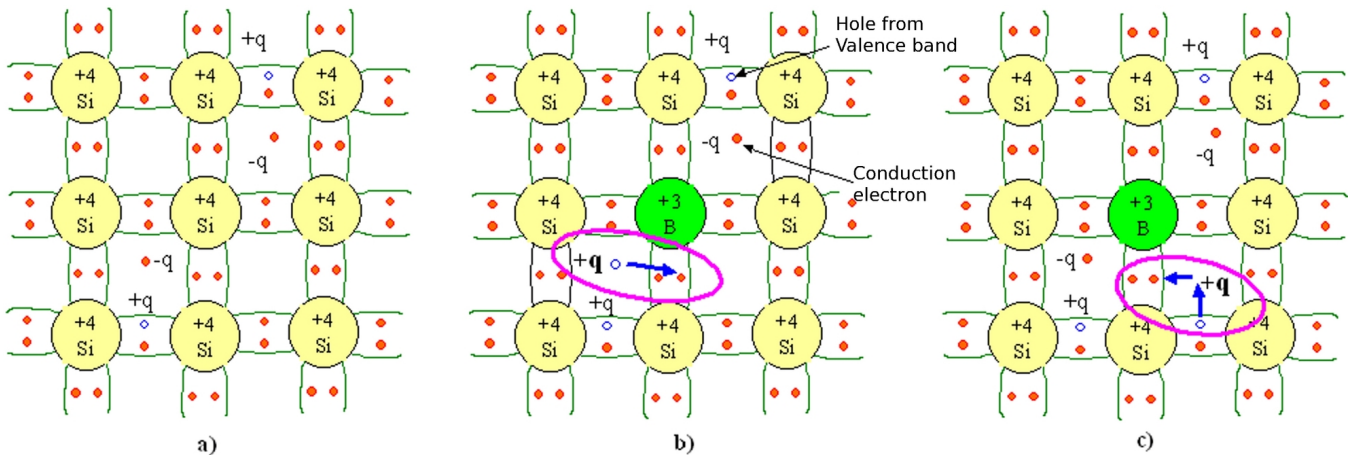
p-type semiconductor structures :

Group IV semiconductors:

Si and Ge
 Acceptors: B and Al

Group III-V semiconductors:

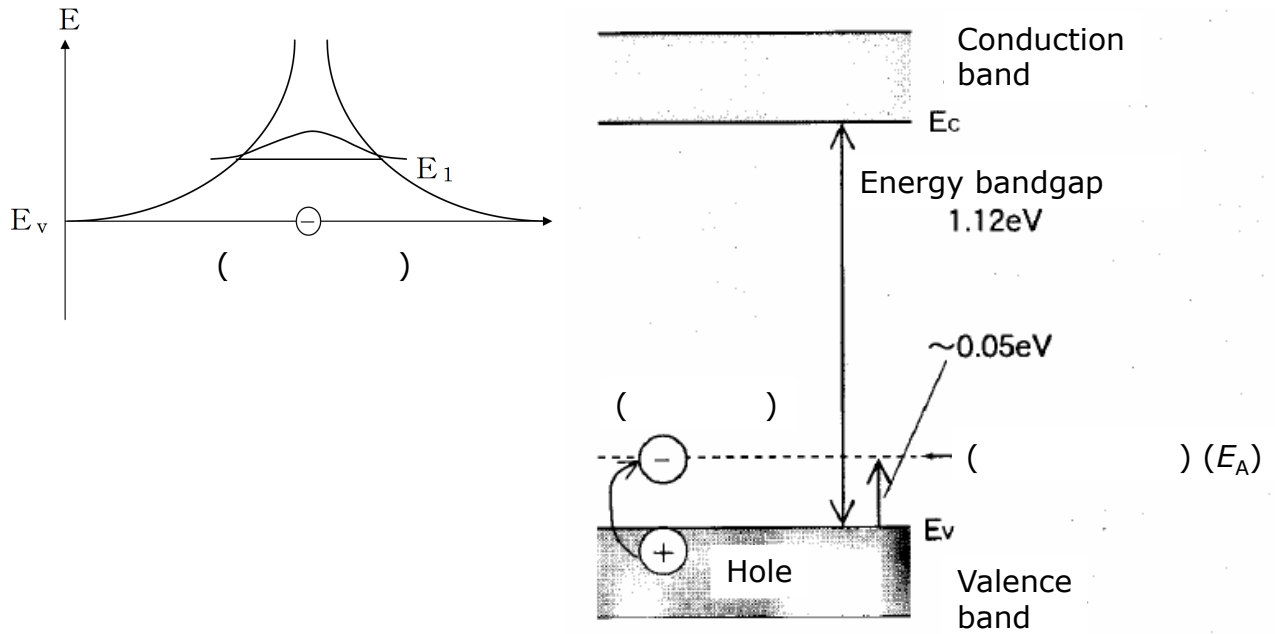
GaAs and GaN
 Acceptors: Be, Zn, Cd and Ge





p-Type Acceptors

Energy potential created by an acceptor ion :

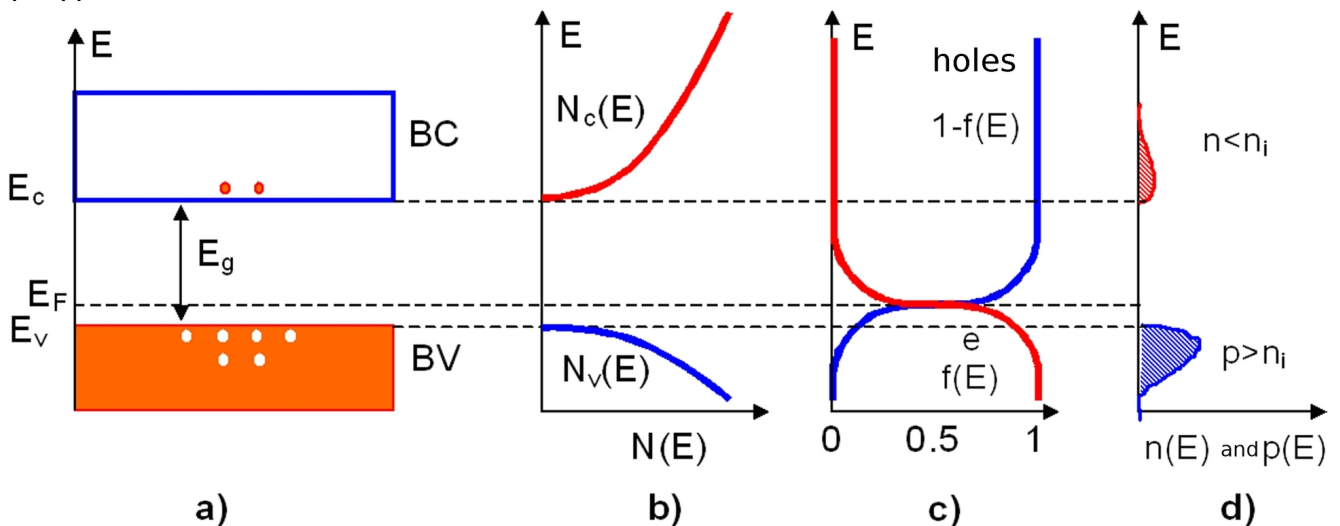


* http://www.phys.chuo-u.ac.jp/labs/wakabaya/lecture/applphys/2C_4.3.pdf



Atomic Structure of p-Type Semiconductors

p-type band structures :



* http://www.optique-ingenieur.org/en/courses/OPI_ang_M05_C02/co/Contenu_04.html



Carrier Number Density

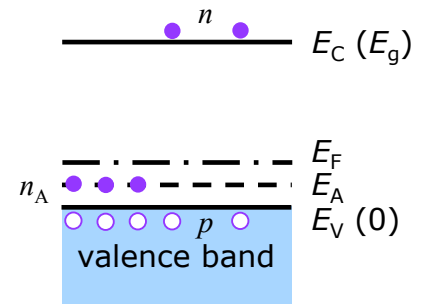
Numbers of holes in the valence band E_V should equal to the sum of those of electrons in the conduction band E_C and in the acceptor level E_A :

$$p =$$

Similar to the intrinsic case,

$$p = N_V f_p(0) \approx N_V \exp\left(-\frac{E_F}{k_B T}\right)$$

$$n = N_C f_e(E_g) \approx N_C \exp\left(-\frac{E_g - E_F}{k_B T}\right)$$



Assuming numbers of neutral acceptors are N_A ,

$$n_A = \frac{N_A}{1 + 2 \exp\left(\frac{E_A - E_F}{k_B T}\right)}$$

For $E_A - E_F > k_B T$, $n_A \approx N_A$

$$\therefore N_V \exp\left(-\frac{E_F}{k_B T}\right) \approx N_C \exp\left(-\frac{E_g - E_F}{k_B T}\right) + N_A$$



Carrier Number Density (Cont'd)

At low temperature, one can assume $p \gg n$, $p \approx n_A$

As n_A is very small, $E_A > E_F$

$$n_A = \frac{N_A}{2} \exp\left(-\frac{E_A - E_F}{k_B T}\right)$$

$$\therefore N_V \exp\left(-\frac{E_F}{k_B T}\right) \approx \frac{N_A}{2} \exp\left(-\frac{E_A - E_F}{k_B T}\right)$$

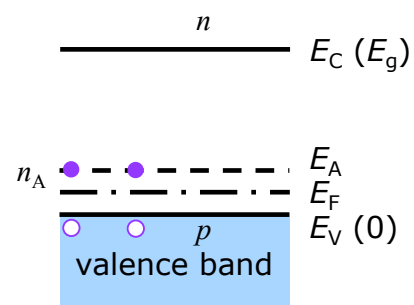
$$\therefore \exp\left(-\frac{E_F}{k_B T}\right) \approx \sqrt{\frac{N_A}{2N_V}} \exp\left(-\frac{E_A}{2k_B T}\right)$$

$$\therefore E_F \approx \frac{k_B T}{2} \ln \frac{2N_V}{N_A} + \frac{E_A}{2}$$

By substituting $N_V \equiv N_{Vp} T^{3/2}$

$$\therefore E_F \approx \frac{k_B T}{2} \ln \left(\frac{2N_{Vp}}{N_A} T^{3/2} \right) + \frac{E_A}{2}$$

For $T \sim$,



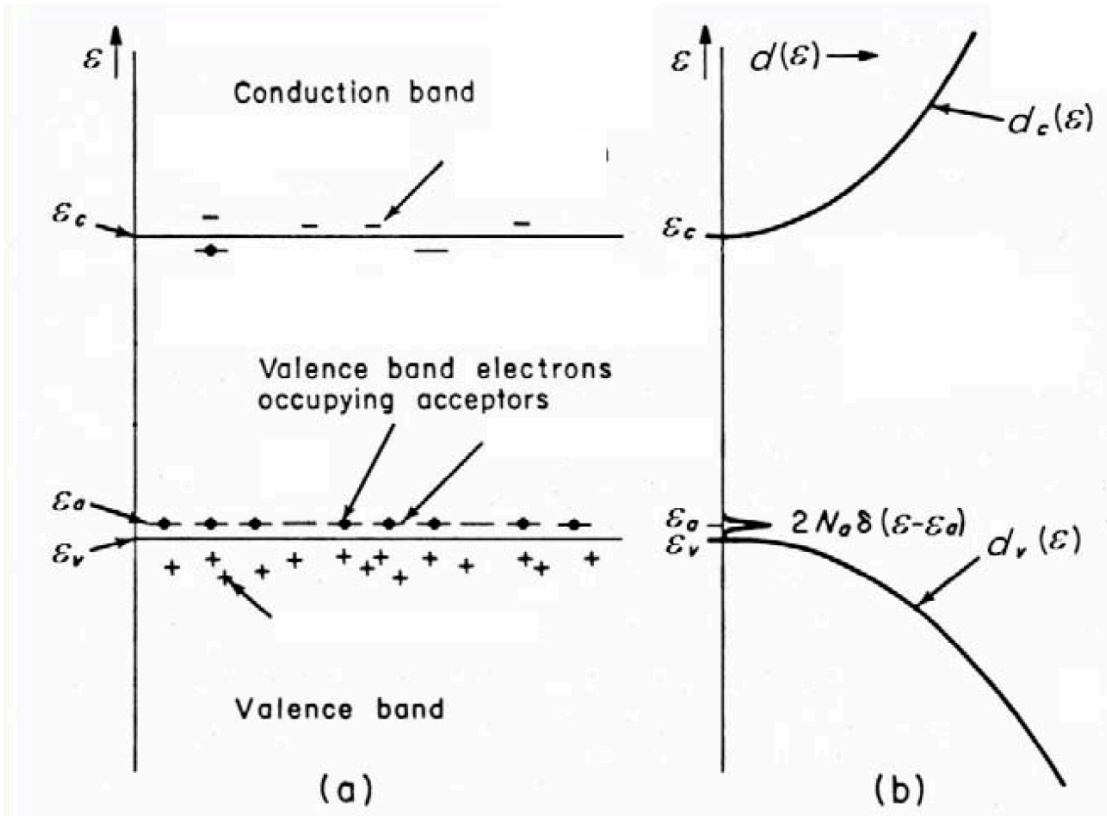
At high temperature, one can assume $n \gg n_A$, $p \approx n$

Similar to the intrinsic case, for $m_e^* = m_p^*$,



Typical Band Structures

Acceptor level near the valence bands :



* http://www.phys.chuo-u.ac.jp/labs/wakabaya/lecture/applphys/2C_4.3.pdf



Atomic Structure of *n*-Type Semiconductors

n-type semiconductor structures :

Group IV semiconductors:

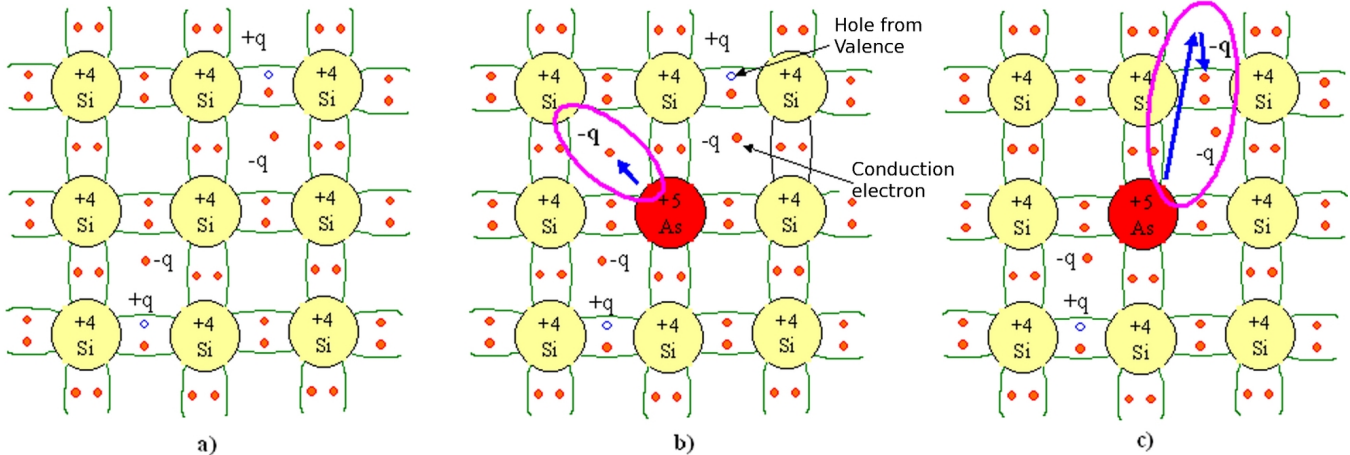
Si and Ge

Donors: P and As

Group III-V semiconductors:

GaAs and GaN

Donors: Se, Te, Si and Ge

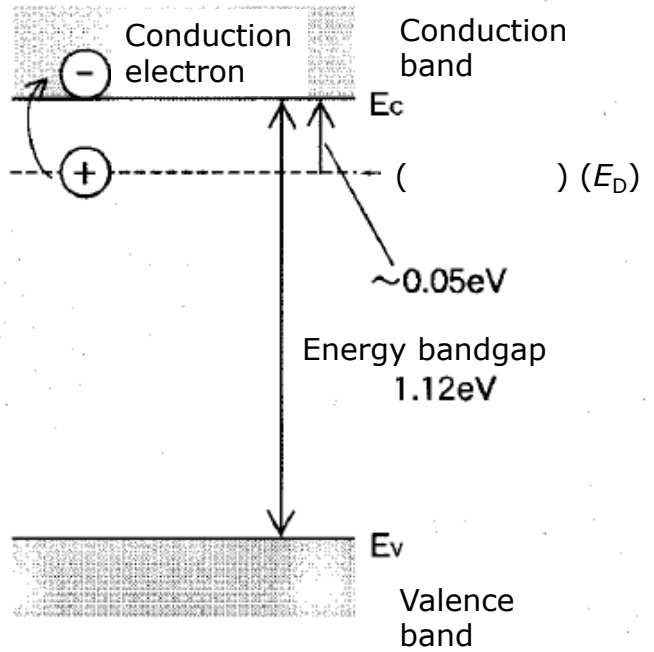
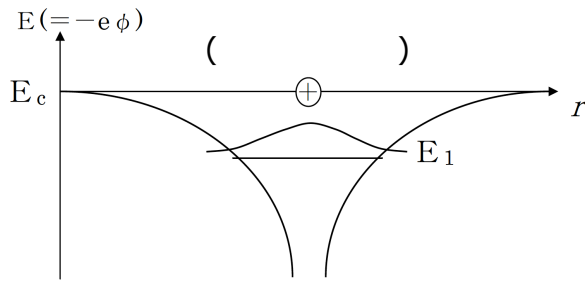


* http://www.optique-ingenieur.org/en/courses/OPI_ang_M05_C02/co/Contenu_04.html



n-Type Donors

Energy potential created by a donor ion :

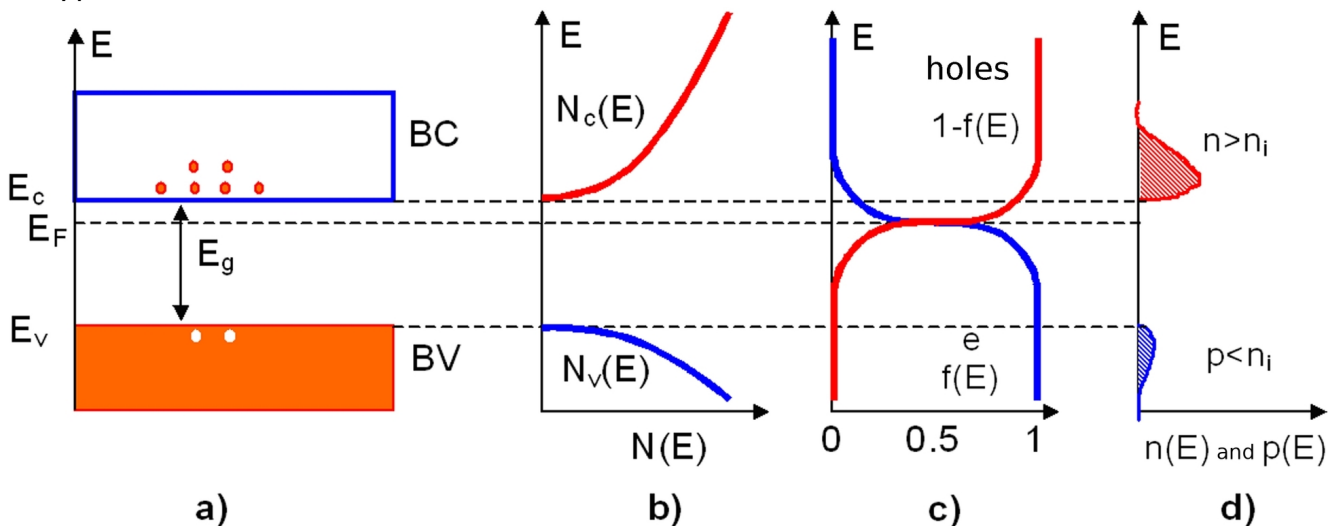


* http://www.phys.chuo-u.ac.jp/labs/wakabaya/lecture/applphys/2C_4.3.pdf



Atomic Structure of n-Type Semiconductors

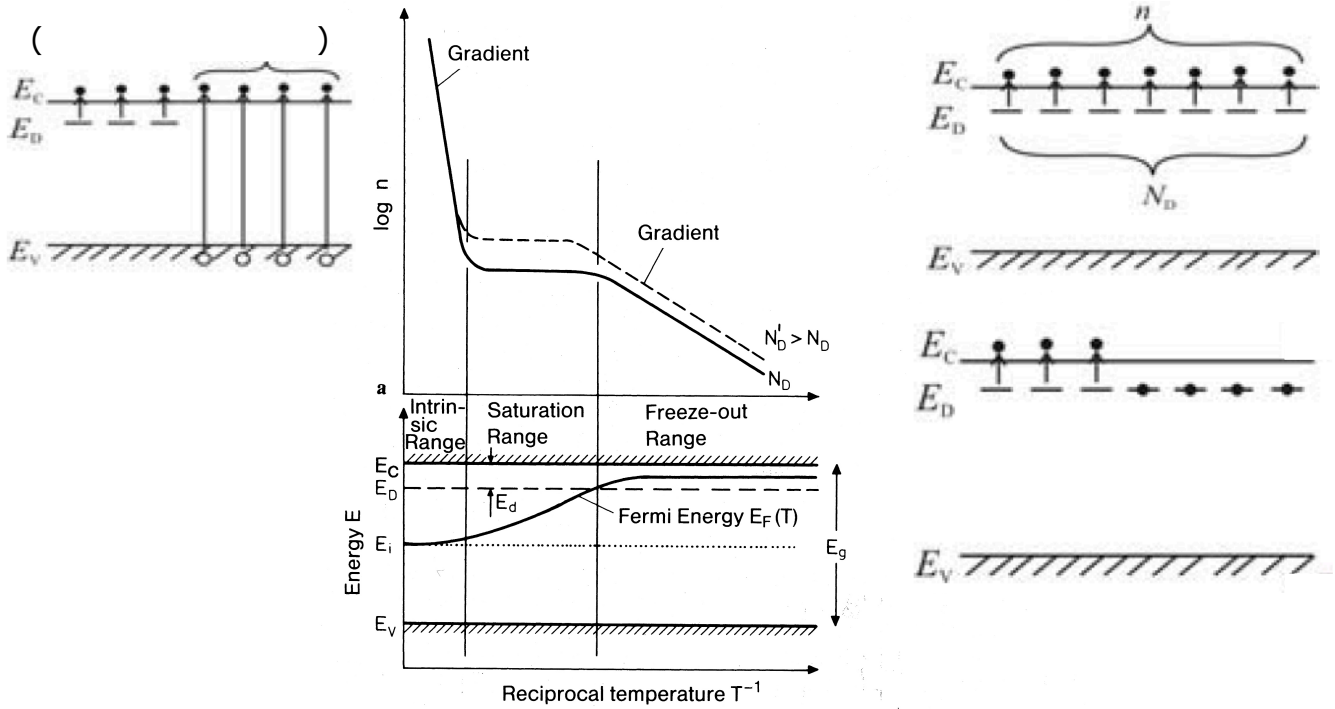
n-type band structures :



* http://www.optique-ingenieur.org/en/courses/OPI_ang_M05_C02/co/Contenu_04.html



Temperature Dependence of an Extrinsic Semiconductor

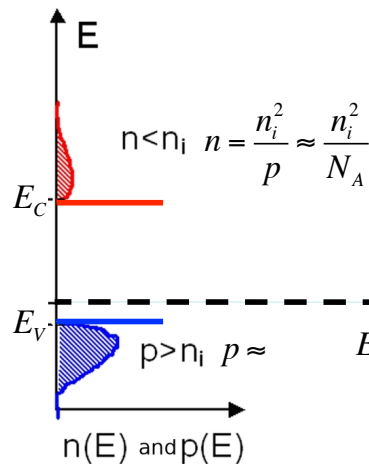


* H. Ibach and H. Lüth, *Solid-State Physics* (Springer, Berlin, 2003);
 ** <http://akita-nct.jp/tanaka/kougi/2007nen/3e/3-4hujunbutu.pdf>

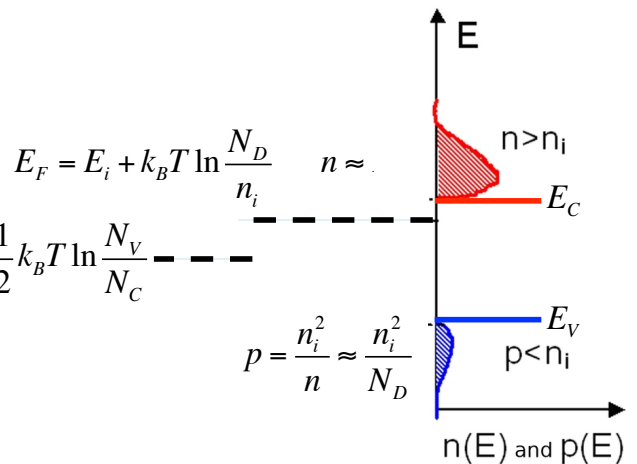


Carrier Densities of Extrinsic Semiconductors

p-type band structure :



n-type band structure :



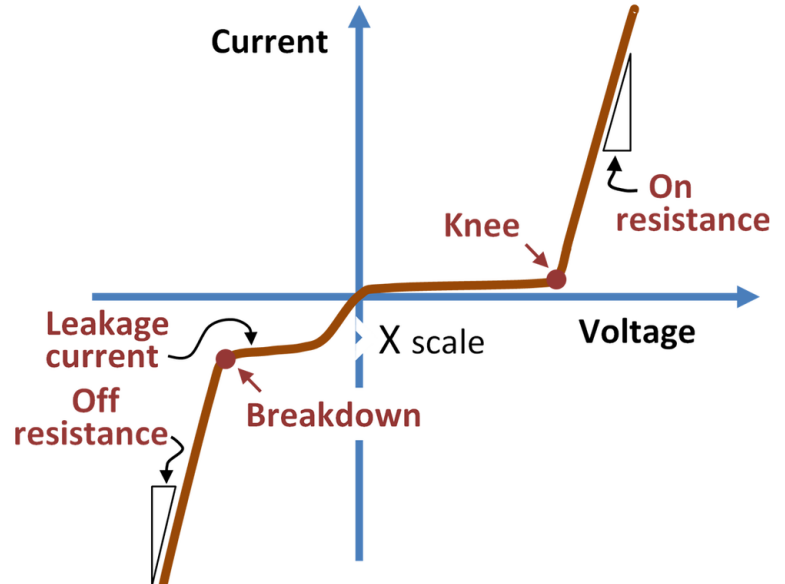
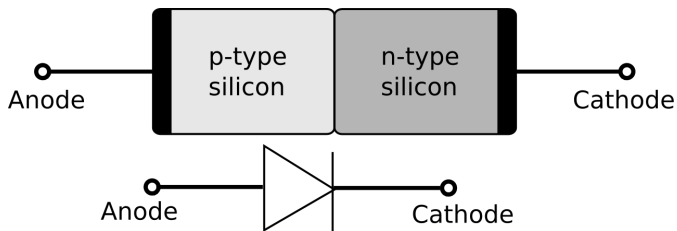


p-n Diode

A junction made by attaching p- and n-doped semiconductors :

Widely used to insulate transistors.

Common circuit to convert ac to dc in a battery charger.



* <http://www.wikipedia.org/>



Exercise 2

For the Silicon material with doping, estimate the dopant concentration (N_D) needed to manufacture a $1 \text{ M}\Omega$ resistor measuring $100 \mu\text{m}$ in length and $5 \mu\text{m}^2$ in cross section.

Assume that the transport of current will be carried out by majority carriers and that for Silicon,
intrinsic carrier density: $n_i = 10^{16} \text{ m}^{-3}$,
mobility of electrons: $\mu_e = 0.135 \text{ m}^2/\text{V}\cdot\text{s}$
and mobility of holes: $\mu_h = 0.05 \text{ m}^2/\text{V}\cdot\text{s}$.

